

INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Not for submission under 37 CFR 1.99)	Application Number	10758966
	Filing Date	2004-01-16
	First Named Inventor	DIANE K. STEWART
	Art Unit	1792
	Examiner Name	ALLAN W. OLSEN
	Attorney Docket Number	F125

U.S.PATENTS

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	1	5639699		1997-06-17	NAKAMURA ET AL.	
	2	5965301		1999-10-12	NARA ET AL.	
	3	6361904		2002-03-26	CHIU	

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	1	NAKAMURA, H. ET AL., "Focused Ion Beam Assisted Etching of Quartz in XeF2 without Transmittance Reduction for Phase Shifting Mask Repair," Japanese Journal of Applied Physics, December 1992, pages 4465-4467, Volume 31, No. 12B, Japan.	<input type="checkbox"/>

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